L Number	Hits	Search Text	DB	Time stamp
15	4	(US-5423944-\$ or US-6326218-\$ or	USPAT;	2003/06/18
		US-6451665-\$).did. or (EP-782177-\$).did.	EPO EPO	15:11
34	5	( =	USPAT	2003/06/18
		US-6451665-\$ or US-6506636-\$ or		15:11
35	7	US-6512182-\$).did. ((US-6326218-\$ or US-6432835-\$ or	HCDAM.	2002/06/10
	'	US-6451665-\$ or US-6506636-\$ or	USPAT; EPO; JPO	2003/06/18 15:12
		US-6512182-\$).did.) or ((US-5423944-\$ or	1210, 010	
		US-6326218-\$ or US-6451665-\$).did. or		
26		(EP-782177-\$).did.)		
36	3	, , , ,	USPAT;	2003/06/18
		US-6451665-\$ or US-6506636-\$ or US-6512182-\$).did.) or ((US-5423944-\$ or	EPO; JPO	15:14
	İ	US-6326218-\$ or US-6451665-\$).did. or		
		(EP-782177-\$).did.)) and wet adj3		
27	252224	(etch\$3)		
37	353394	platinum pt ruthenium ru rhodium rh palladium pd iridium ir	USPAT;	2003/06/18
38	5006		EPO; JPO USPAT;	15:13 2003/06/18 .
		palladium pd iridium ir ) and wet adj3	EPO; JPO	15:14
		(etch\$3)		
39	918		USPAT;	2003/06/18
		palladium pd iridium ir ) and wet adj3 (etch\$3)) and (NaCl "sodium chloride" KCl	EPO; JPO	15:17
		"potassium chloride" CaCl "calcium		
		chloride" HCl "hydrochloric acid" "liquid		
		salt")		
40	320985		USPAT;	2003/06/18
		chloride" CaCl "calcium chloride" HCl "hydrochloric acid" "liquid salt"	EPO; JPO	15:18
41	31912	(NaCl "sodium chloride" KCl "potassium	USPAT;	2003/06/18
		chloride" CaCl "calcium chloride" HCl	EPO; JPO	15:18
		"hydrochloric acid" "liquid salt") same		
		(platinum pt ruthenium ru rhodium rh palladium pd iridium ir )		
42	4783	(NaCl "sodium chloride" KCl "potassium	USPAT;	2003/06/18
		chloride" CaCl "calcium chloride" HCl	EPO; JPO	15:21
		"hydrochloric acid" "liquid salt") adj10		
		(platinum pt ruthenium ru rhodium rh		1
43	4	palladium pd iridium ir )   (NaCl "sodium chloride" KCl "potassium	USPAT;	2003/06/18
		chloride" CaCl "calcium chloride" HCl	EPO; JPO	15:22
		"hydrochloric acid" "liquid salt") adj10		
		(platinum pt ruthenium ru rhodium rh		
		palladium pd iridium ir ) adj15 (wet adj3 etch\$3)		
44	65	(wet adj3 etch\$3) adj5 (platinum pt	USPAT;	2003/06/18
		ruthenium ru rhodium rh palladium pd	EPO; JPO	16:17
1 E	,	iridium ir )		
45	1	5515984.pn.	USPAT;	2003/06/18
46	0	(wet adj3 etch\$3) adj5 "noble metals"	EPO; JPO USPAT;	15:30   2003/06/18
	_	-	EPO; JPO	16:18
47	56	(etch\$3) adj5 "noble metals"	USPAT;	2003/06/18
_	294959	capacitor	EPO; JPO	16:18
	254535	capacitor	USPAT; EPO; JPO	2003/06/17 18:25
-	353394	platinum pt ruthenium ru rhodium rh	USPAT;	2003/06/18
		palladium pd iridium ir	EPO; JPO	15:13
-	12300	(03 ozone) and (water steam H2O) and	USPAT;	2003/06/17
		(halgenide Fluoride Chloride Bromide iodide)	EPO; JPO	18:28
-	448	(03 ozone) and (water steam H2O) and	USPAT;	2003/06/17
		(halgenide Fluoride Chloride Bromide	EPO; JPO	18:39
		iodide) same (etch etching etcher	:	
_	20324	etchant) capacitor and (platinum pt ruthenium ru	IICDAM.	2002/06/17
	20024	rhodium rh palladium pd iridium ir)	USPAT; EPO; JPO	2003/06/17 18:29
		· · · · · · · · · · · · · · · · · · ·		

Γ=	44	(capacitor and (platinum at mut)	Titana		
	33	(capacitor and (platinum pt ruthenium ru	USPAT;	2003/06/18	
		rhodium rh palladium pd iridium ir)) and	EPO; JPO	15:12	
	ļ	((03 ozone) and (water steam H2O) and			
		(halgenide Fluoride Chloride Bromide		ŀ	
	İ	iodide) same (etch etching etcher			
		etchant))			
_	27	1 (TO TESTION DAME (WALCE DECAM 1120) Same	USPAT;	2003/06/17	
		(halgenide Fluoride Chloride Bromide	EPO; JPO	18:48	
		iodide halogen F2 Cl2 Br2 I2) same (etch			
		etching etcher etchant)			
-	6	8-153707	USPAT	2003/06/18	
				12:18	
-	0	8-153707	JPO	2003/06/18	- 1
				12:20	
-	0	08-153707	JPO	2003/06/18	- [
				12:20	- 1
-	0	"08-153707"	JPO	2003/06/18	-
				12:20	
-	0	"manufacturing method for semiconductor	JPO	2003/06/18	1
		device".ti.		12:21	
-	0	"manufacturing method for semiconductor	JPO	2003/06/18	ı
		device"		12:21	
-	178515	takeshi.inv.	JPO	2003/06/18	
				12:21	- [
-	121	takeshi.inv. and Ruthenium	JPO	2003/06/18	- 1
				12:21	ı
-	1	(takeshi.inv. and Ruthenium) and SOG	JPO	2003/06/18	- [
				12:22	ı